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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/519,129	03/06/2000	KENJI UEDA	A-346	7895
802 7	590 03/07/2002			
DELLETT AND WALTERS			EXAMINER	
SUITE 1101	RTH AVENUE		ANGEBRANNE	OT, MARTIN J
PORTLAND,	OR 97204		ART UNIT	PAPER NUMBER
			1756	10
			DATE MAILED: 03/07/2002	

Please find below and/or attached an Office communication concerning this application or proceeding.

·		Application No.	Applicant(s)
	_		Applicant(s)
Office Action Summary		09/519,129	UEDA ET AL.
	v r.v.o vanimary	Examiner	Art Unit
	The MAILING DATE of this communication a	Martin J Angebranndt	1756
Period fo		ppears on the cover sheet wit	ui die correspondence address
THE in the control of	ORTENED STATUTORY PERIOD FOR REP MAILING DATE OF THIS COMMUNICATION nsions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a reperiod for reply is specified above, the maximum statutory perion to reply within the set or extended period for reply will, by state the received by the Office later than three months after the mailed patent term adjustment. See 37 CFR 1.704(b).	1.136(a). In no event, however, may a reeply within the statutory minimum of thirty or will apply and will expire SIX (6) MON tute, cause the application to become AB.	eply be timely filed (30) days will be considered timely. THS from the mailing date of this communication. ANDONED (35 U.S.C. & 133).
1)🛛	Responsive to communication(s) filed on 30	O July 2001 and 02 January 2	<u> 2002</u> .
2a)⊠	This action is FINAL . 2b)	This action is non-final.	
3)	Since this application is in condition for allocolosed in accordance with the practice under	wance except for formal mat er <i>Ex par</i> te <i>Quayle</i> , 1935 C.E	ters, prosecution as to the merits is 0. 11, 453 O.G. 213.
Dispositi	on of Claims	•	*
	Claim(s) 1-11 is/are pending in the application		
	4a) Of the above claim(s) is/are withdr	rawn from consideration.	
	Claim(s) is/are allowed.		
	Claim(s) 1-11 is/are rejected.		
	Claim(s) is/are objected to.		
	Claim(s) are subject to restriction and on Papers	or election requirement.	
9) 🗌 .	The specification is objected to by the Examir	ner.	
10) 🔲 🗆	The drawing(s) filed on is/are: a)□ acc	epted or b) objected to by th	e Examiner.
	Applicant may not request that any objection to	the drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).
11) 🔲 -	The proposed drawing correction filed on		sapproved by the Examiner.
	If approved, corrected drawings are required in r		
•	The oath or declaration is objected to by the E	Examiner.	
Priority u	nder 35 U.S.C. §§ 119 and 120		
13)	Acknowledgment is made of a claim for foreign	gn priority under 35 U.S.C. §	119(a)-(d) or (f).
a)[☐ All b) ☐ Some * c) ☐ None of:		
	1. Certified copies of the priority documer	nts have been received.	
	2. Certified copies of the priority documer		•
	 Copies of the certified copies of the pri application from the International B ee the attached detailed Office action for a lis 	Bureau (PCT Rule 17.2(a)).	-
14) 🗌 A	cknowledgment is made of a claim for domes	stic priority under 35 U.S.C. §	119(e) (to a provisional application).
15) <u> </u>	☐ The translation of the foreign language p cknowledgment is made of a claim for domes		
Attachment			·
2) 🔲 Notice	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice of In	ummary (PTO-413) Paper No(s) formal Patent Application (PTO-152)
E. Patent and Tra FO-326 (Rev	4 . 4	Action Summary	Part of Paper No. 10

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The response provided by the applicant has been read and given careful consideration. Responses to the arguments offered by the applicant are presented after the first rejection to which they are directed. Rejections of the previous office action not appearing below are withdrawn based upon the arguments and amendments of the applicant. The drawing changes are approved. The translation provided by the applicant is appreciated and made of record on the PTO-892.

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless --

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.
- 3 The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4 Claims 1,(7/1), 8 and (10-11/8) are rejected under 35 U.S.C. 102(b) as being fully anticipated by Brady et al. '546.

Brady et al. '546 teaches a wafer substrate which is coated with a photoresist (photopolymer) material. The photoresist laminate is precut, with the photoresist sandwiched between a MYLAR and a polyolefin sheet and bonded to a transport tape. The polyolefin layer is removed and the exposed portion of the photoresist is contacted with the wafer and adhered thereto.

The limitations of claims 10 and 11 are considered intended use as the means are described as means for handling these films and the films are not described as part of the apparatus. The examiner holds that the semiconductor/silicon substrates described inherently are able to function as supports for holographic recording materials.

The applicant argues that the iterative feeding of the sheets is not taught by the reference as a backing tape is used. The examiner holds that the claims currently embrace the example of the reference as it feeds the resist decals cut from the sheets iteratively/repeatedly via the carrier tape. The rejection stands.

5 Claims 1,(7/1), 8 and (10-11)/8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Brady et al. '546, further in view of Ueda JP 09-054539 and Smith et al. '778.

Ueda JP 09-054539 teaches holographic dry plates which comprise either a supporting film, a photopolymeric holographic recording medium, a substrate, a tacky adhesive layer and a light absorption film or a supporting film, a photopolymeric holographic recording medium, a substrate, a light absorbing adhesive film and a substrate. The peeling of the separator from the photosensitive layer and the support and contacting it with one side of a support and peeling the separator from a tacky adhesive layer and light absorption film and contacting it with the other side of the support is disclosed. (abstract).

Smith et al. '778 teaches that for dry film resists various materials may be used as supports and that these supports may be provided with antihalation, anchor or adhesive layers.

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The examiner holds that the limitations of claims 10 and 11 are considered intended use as the means are described as means for handling these films and the films are not described as part of the apparatus, but anticipates the possibility that the applicant will add the film as part of the apparatus limitations.

It would have been obvious to one skilled in the art to use the means disclosed by Brady et al. '546 in the process of Ueda JP 09-054539 with a reasonable expectation of achieving the desired result based upon the disclosed functionality within the photoresist handling art and with the advantage of continuous processing and upon the teaching within Smith et al. '778 that the use of adhesive, anchor or antihalation layers is desirable for use with dry resist materials.

8 Claims 1,2,(7/1,2), 8-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Brady et al. '546, in view of Garber '221 and Platzer et al. '873.

Garber '221 teaches the lamination of photoresist material in a vertical orientation and cutting of the film to fit. The benefit of the more vertical orientation is that the resist is applied without wrinkles or the like.

Platzer et al. '873 teaches an apparatus for peeling carrier films from photoresists and the like which require little horizontal space and does not require the use of an adhesive tape or element to perform the peeling. (2/67-3/5).

It would have been obvious to one skilled in the art to use the means disclosed by Garber '221 and Platzer et al. '873 in place of those used in the process of Brady et al. '546 based upon the disclosure of equivalent function and the reduced space requirements and wrinkling disclosed as advantages or to use orient the peeling and lamination apparatus of Brady et al. '546 to gain the advantages attributed to this orientation by Garber '221 and Platzer et al. '873.

The rejection stands for the reasons provided above without further comment as no further arguments were directed at this rejection.

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however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Nemoto et al. 457 (3/7-13), Sinta et al. '102 (1/54-65 and 2/46-55) teach the use of antihalation layers with photoresists.

Chao et al. (4/7), Schlesinger et al. '449 (14/15) and Wreede '923 (4/8) teach the use of semiconductor wafers/substrates as useful supports for holographic recording materials.

Freisitzer et al. '450 is cumulative to Brady et al. '546.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Martin Angebranndt whose telephone number is (703) 308-4397.

I am normally available between 7:30 AM and 5:00 PM, Monday through Thursday and 7:30 AM and 4:00 PM on alternate Fridays.

If repeated attempts to reach me are unsuccessful, my supervisor may be reached at (703) 308-2464.

Facsimile correspondence should be directed to (703) 872-9311.

Any inquiry of a general nature or relating to the status of this application should be directed to the Group receptionist whose telephone number is (703) 308-0661.

Martin J/Angebranndt

Primary Examiner, Group 1750

March 5, 2002